

**AMENDMENTS TO THE SPECIFICATION**

1. Please replace paragraph [00183] with the following paragraph.

[00183] The mask writing process may be used with a mask inspection process. For example, the inspection process disclosed in co-pending U.S. Application Serial No. 10/620,284, filed July 14, 2003, which claims the benefit of U.S. Provisional Application No., 60/395,467, filed July 12, 2002, and which is incorporated herein by reference in its entirety, may be used to inspect a mask written with a process as disclosed herein.

2. Please replace paragraph [00155] with the following paragraph.

[00155] The mask element 518 and its contextual information may then pass to an analysis block 306, wherein its context may be evaluated and its mask writing priority determined manually or by a computer-aided automated process. In such an analysis block 306, as a high priority element, criteria for priority, criticality, dimensions, location, and sensitivity to defects, among others, may be applied to 518 manually or via automated process of comparison to determine its mask writing context and priority relative to the other mask elements. In other words, block 306 may determine in what order and with what precision 518 will be written. RET and other enhancements may also be added, such as OPC features 520, 522, 524, 526, 528 and 530, if not already included, either manually or by computer-aided process, based on element context and priority. Further, shaped-beam parameters of the writing tool may be adjusted accordingly for high resolution.

### Marked-Up Replacement Paragraph

1. The following paragraph shows the changes to paragraph [00183].

[00183] The mask writing process may be used with a mask inspection process. For example, the inspection process disclosed in co-pending ~~Atty. Docket No. CA7010502001~~, U.S. ~~Application~~ Serial No. ~~XX/XXX,XXX-10/620,284~~, filed July 14, 2003, which claims the benefit of U.S. ~~Provisional~~ Application No., 60/395,467, filed July 12, 2002, and which is incorporated herein by reference in its entirety, may be used to inspect a mask written with a process as disclosed herein.

2. The following paragraph shows the changes to paragraph [00155].

[00155] The mask element 518 and its contextual information may then pass to an analysis block 306, wherein its context may be evaluated and its mask writing priority determined manually or by a computer-aided automated process. In such an analysis block 306, as a high priority element, criteria for priority, criticality, dimensions, location, and sensitivity to defects, among others, may be applied to 518 manually or via automated process of comparison to determine its mask writing context and priority relative to the other mask elements. In other words, block 306 may determine in ~~what~~ what order and with what precision 518 will be written. RET and other enhancements may also be added, such as OPC features 520, 522, 524, 526, 528 and 530, if not already included, either manually or by computer-aided process, based on element context and priority. Further, shaped-beam parameters of the writing tool may be adjusted accordingly for high resolution.